

In The Title:

Please amend the title as follows:

~~A METHOD FOR FABRICATING AN INTERFERENCE DISPLAY UNIT~~

In The Specification:

Please amend the paragraph on page 11, beginning at line 10, as follows:-

Please referring to figure 6B, the posts 616, 618, 620 and 622 are defined by patterning the material layer 614 during a photolithographic process. The posts 616, 618, 620 and 622 have supports 6161, 6181, 6201 and 6221 disposed in the openings 606, 608, 610 and 612, and the posts 616, 618, 620 and 622 have arms 61226162, 6182, 6183, 6202, 6203 and 6222. The length of arms 61226162, 6182, 6183, 6202, 6203 and 6222 is same. Therefore, the area of the optical interference display units 630, 632 and 634 for reflecting incident light is similar.

Please amend the paragraph on page 11, beginning at line 17, as follows:-

Reference is next made to figure 6C. A first electrode layer 624 is formed on the sacrificial layer 604 and the arms 61226162, 6182, 6183, 6202, 6203 and 6222. Next, a second electrode layer 626 is formed on the first electrode layer 624, which is located on the optical interference display units 632 and 634. Then, a third electrode layer 628 is formed on the second electrode layer 626 which is located on the optical interference display unit 634. Reference is further made to figure 6C. The first electrode layer 624 on the optical interference display unit 630 is used as the second electrode 636 of the optical interference display unit 630, the first electrode layer 624 and the second electrode layer 626 on the optical interference display unit 632 are used as the second electrode 638 of the optical interference display unit 632, and the first electrode layer 624, the second electrode layer 626 and the third electrode layer 628 on the optical interference display unit 634 are used as the second electrode 640 of the optical interference display unit 634.